IN AN APPLICATION Applicant: Pere ROCA I CABARROCAS et al. (Use several sheets if necessary) Filing Date: Group Art Unit:	
13	
August 8, 2005	
U.S. PATENT DOCUMENTS	
Examiner Document Number Date Name Class Subclass Filing d	
Initial	nate
/D.W./ 6,017,779 1/25/2000 MIYASAKA	
/D.W./ 6,078,059 6/20/2000 NAKATA	
FOREIGN PATENT DOCUMENTS	
Examiner Document Number Date Country Class Subclass Transl	ation
Initial Yes EP 0 609 867 8/10/1994 EUROPE	No
EP 0 609 867 8/10/1994 EUROPE	
	505 ₀₀₀₀
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.) ROCA I CABARROCAS P ET AL: "STABLE MICROCRYSTALLINE SILICON THIN-FILM TRANSISTOI	
DECEMBER BY THE LAVED BY LAVED TECHNIQUES TOURNAL OF ADDITION DUVOICO, AMEDICA	
/D.W./ INSTITUTE OF PHYSICS. NEW YORK, US, vol. 86, no. 12, 15 December 1999 (1999-12-15), pages	
7079-7082, XP000928312 ISSN: 0021-8979 cited in the application page 7079 YOUNG-BAE PARK ET AL: "EFFECT OF HYDROGEN PLASMA PRECLEANING ON THE REMOVAL	OF
/D W / INTERFACIALAMORPHOUS LAYER IN THE CHEMICAL VAPOR DEPOSITION OF	
MICROCRYSTALLINE SILICON FILMS ON SILICON OXIDE SURFACE" APPLIED PHYSICS LETTER AMERICAN INSTITUTE OF PHYSICS. NEW YORK, US, vol. 68, no. 16, 15 April 1996 (1996-04-15),	RS,
pages 2219-2221, XP000585161 ISSN: 0003-6951 page 2219	
EXAMINER: (David Mindon) DATE CONSIDERED	***************
EXAMINER: /Daniel Whalen/ DATE CONSIDERED 03/23/2009	
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation to in conformance and not considered. Include copy of this form with next communication to the applicant.	on it

* English language abstract provided for the Examiner's convenience

BC/gw